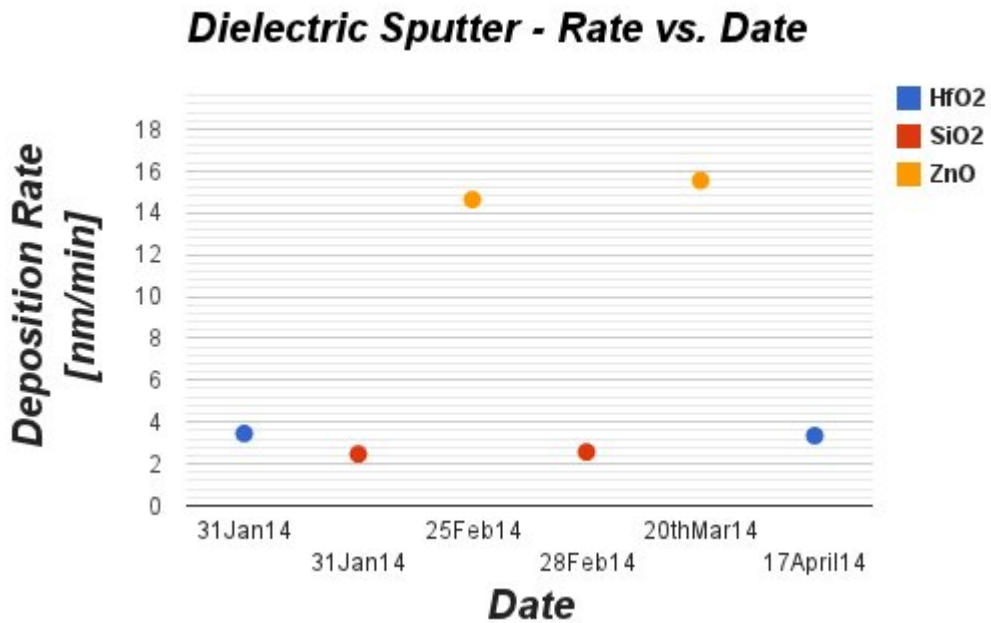
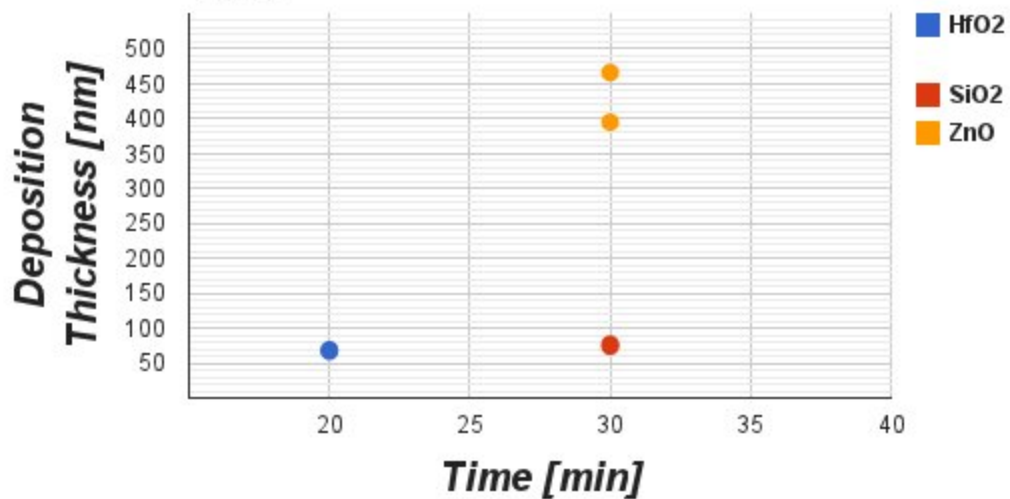


# IITBNF – Equipment Performance

Equipment	Location	Ambience	Contamination Category
Dielectric Sputter	Micro 1	Semiclean	Au Contaminated



### Dielectric Sputter - Thickness vs. Time



Target	SiO2, HfO2, ZnO	Pressure with Ar [mbar]	$2.2 \cdot 10^{-2}$
Base Vacuum [mbar]	$3.9 \cdot 10^{-2}$	RF Power [W]	150
High Vacuum [mbar]	$5 \cdot 10^{-5}$	Reflected Power [W]	0
Gases	Ar		